# ATP Annual Meeting 1999

3M/BFGoodrich: Project *TOPCAT*<u>Tailoring Optical Polymers through a Novel CAT</u> alysis System

Lightwave Microsystems/BFGoodrich: Project OASIS

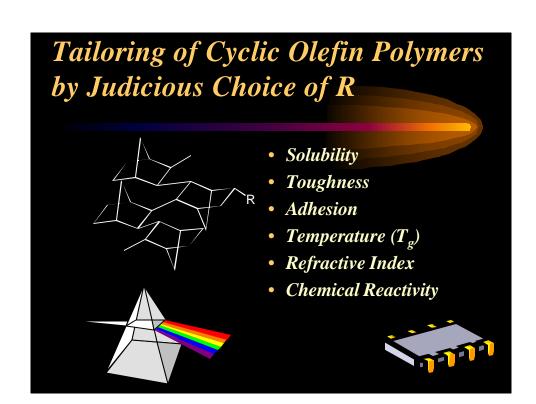
<u>Optical Polymers and Manufacturing Processes for Low-Cost WDM Devices And SYS</u>tems

#### Outline

- Background
- Project TOPCAT
- Project OASIS
- Spin-Offs
- Conclusions

### Cyclic Olefin Polymers

- BFGoodrich...A Leader in Cyclic Olefin Chemistry
  - Major R&D Focus Area for Over 20 Years
  - Encompasses Monomer, Polymer and Catalysis
     Technology
  - Supports Several BFG Businesses
  - New Class of High Performance Polymers with Outstanding Optical and Dielectric Performance



#### "Tailored Optical Polymers Through a Novel Catalyst System"

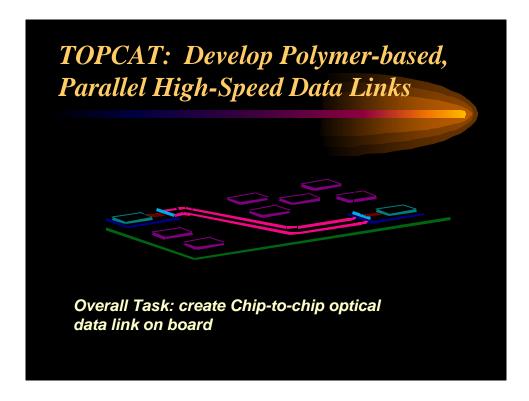


Joint project with 3M

#### 3M/BFGoodrich: Project TOPCAT

#### **OBJECTIVES:**

- Develop Novel Catalysis Systems
- Tailor New High Performance Optical Materials
- Implement New Designs and Components to Construct High Performance Optical Communication Links



# Material Targets - TOPCAT

- < 0.1 dB/cm attenuation at 850 nm
- $\mathbf{D}i > 0.02$
- In constant over temperature range
- Solder Reflow Compatible
- > 2,000 hours at 125 C in air

## TOPCAT: Program Status

- Completed 4th Year Review of this 5 Year Program
- Demonstrated Bench Scale Working Wave-Guides
- Program Meeting Milestones
- 1 US Patent and 7 Applications
- Major Spin-Off Opportunities Defined

# Optical Polymers and Manufacturing Processes for LowCost WDM Devices and Systems Joint with Lightwave Microsystems OASIS

# Lightwave Microsystems/BFGoodrich: Project OASIS

#### **OBJECTIVES:**

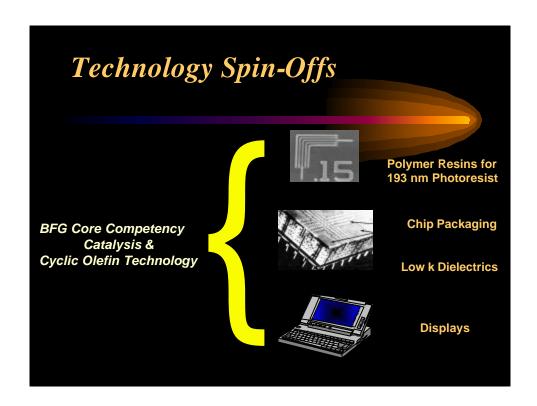
- Low Optical Loss Polymers at 1300-1550 nm
- Add Drop Wave Division Multiplexing Systems
- Low-Cost Process for Manufacture

#### Material Targets - OASIS

- < 0.1 dB/cm at 1550 nm
- 0.006 > 2h > 0.017 (0.4 to 1.2 %)
- Core index should match glass
  - -n = 1.4450 @ 1550 nm
- Lifetime of 200,000 hours at 150 C (inert atmosphere)

# OASIS: Program Status

• Program in it's First Quarter Following Repositioning of the Objectives at Kick-Off Meeting



#### Technology Spin-Offs

#### **Polymer Resins for 193 nm Photoresist**

- Transparency at 193 nm
- Robust towards Reactive Ion Etch
- Hydrophylic and Hydrophobic Monomer Combinations (Tailoring)
- Developmental Sales to Major Suppliers
  - DUVCOR™ Photoresist Materials

#### Technology Spin-Offs

#### **Chip Packaging**

- High Temperature
- Low Moisture Adsorbtion
- Low Dielectric
- Monomer Combinations Selected to fit Balance of Properties Needed (Tailoring)
- Products Under Joint Development
  - AVATREL™ Dielectric Materials

#### Technology Spin-Offs

#### Low k Dielectrics

- Joint Developments with Georgia Institute of Technology (NSF Grant)
  - Atrium<sup>™</sup> Nano-foam Materials
  - Unity<sup>™</sup> 400 Air-Gap Materials

## Technology Spin-Offs

#### **Displays**

- US Display Consortium Grant to Produce ITO/Barrier Coated Substrates (\$2.6M)
  - Appear™ Optical Polymers

# Value of ATP

- Disciplined Focus on Definition of Customer's (JV Partner) Need and Business Opportunity
- Emphasis on Sound Technology Planning
- Fosters Intnmate Partner Relationships
- Constant Communication: Daily/Weekly/Qtrly
- Multiyear Corporate Matching Commitment
  - Multiyear Budget
  - Corporate Resource Leveraging
  - Flexibility of Strategic Shift within Limits
- Internal Credibility